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High-k Materials and Devices 2014

Guest Editor:

Prof. Dr. Durga Misra

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Deadline for manuscript submissions:

closed (15 January 2014)

Message from the Guest Editor

Dear Colleagues,

Advanced gate stacks with high dielectric constant materials (high-k) for complementary metal-oxidesemiconductor (CMOS) and memory applications in sub-22 nm feature size integrated circuits have been a subject of intense research in recent years. The main focus of the forthcoming special issue is to present a comprehensive overview to our readers by assembling state-of-the-art research articles and reviews on processing characterization of high-k gate material. The topics covered by this special issue include high-k materials and deposition methods; Deposition on high-mobility substrate such as Ge. GaAs, and other III-V compounds: Interface passivation of substrate/high-k interface; Reliability of material; Characterization techniques Application to non-volatile memory systems.

Prof. Dr. Durga Misra Guest Editor













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Editor-in-Chief

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Message from the Editor-in-Chief

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